

Form 101-101 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1599	SERIAL NO. 09/820,468
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT Werner Juengling et al.	
		FILING DATE March 28, 2001	GROUP 2812

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 PATENT & TRADEMARK OFFICE

U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	5,494,858	02-1996	Gnade et al.			
	AB	5,723,368	03-1998	Cho et al.			
	AC	5,380,679	01-1995	Kano			
	AD	5,967,804	10-1999	Yoshizawa et al.			
	AE	5,981,085	11-1999	Ninomiya et al.			
	AF	6,347,446 B1	02-2002	Luthra et al.			
	AG	5,298,311	03-1994	Bentson et al.			
	AH	6,245,439 B1	06-2001	Yamada et al.			
	AI						
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FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation		
					Yes	No	
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
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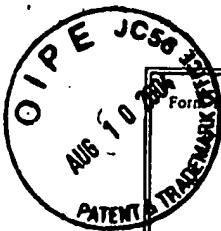
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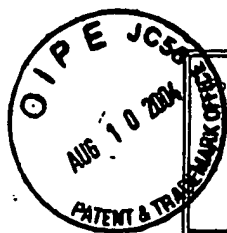
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*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	4,843,034	7/27/1989	Hemdon et al.			
	AB	5,750,415	5/12/1998	Gnade et al.			
	AC	5,858,871	1/12/1999	Jeng			
	AD	6,319,852 B1	11/20/2001	Smith et al.			
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FOREIGN PATENT DOCUMENTS							
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1599		PRIORITY SERIAL NO. 09/115,339	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Werner Juengling et al.			
				PRIORITY FILING DATE July 14, 1998		PRIORITY GROUP 2813	
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
PH	AA	3,919,060	11/11/75	Pogge et al.			
	AB	3,979,230	9/7/76	Anthony et al.			
	AC	3,998,662	12/21/76	Anthony et al.			
	AD	4,063,901	12/20/77	Shiba			
	AE	4,180,416	12/25/79	Brock			
	AF	5,488,015	1/30/96H	Evemann et al.			
	AG	5,496,773	3/5/96	Rhodes et al.			
	AH	5,525,857	6/11/96G	Maede et al.			
	AI	5,527,737	6/18/96J	eng			
	AJ	5,583,078	12/10/96	Osenbach			
PH	AK	5,599,745	2/4/97	Reinberg			
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	AL						
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	AN						
	AO						
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PH	AR		HOMMA, TETSUYA, "Low Dielectric Constant Materials and Methods for Interlayer Dielectric Films in Ultralarge-Scale Integrated Circuit				
			Multilevel Interconnections", <u>Materials Science & Engineering</u> , R23, pp. 243-285 (1998)				
PH	AS		ABSTRACT: Townsend, P.H., et al., "SILK Polymer Coating With Low Dielectric Constant and High Thermal Stability for ULSI Interlayer				
			Dielectric", <u>The Dow Chemical Company</u> , Midland, MI, 9 Pages, (Undated)				
	AT		PRODUCT BROCHURE and MATERIAL SAFETY DATA SHEET, "Interlayer Dielectric", <u>JSR Microelectronics</u> , 12 Pages (1997)				
EXAMINER <i>[Signature]</i>				DATE CONSIDERED 10/8/04			
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						PRIORITY GROUP 2813	
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
MBC	AA	5,629,238	5/13/97C	Pol et al.			
	AB	5,670,828	9/23/97C	Heung et al.			
	AC	5,691,565	11/25/97	Manning			
	AD	5,691,573	11/25/97	Avanzino et al.			
	AE	5,773,363	6/30/98D	Gerdtan et al.			
	AF	3,954,523	05/76	Magdo et al.	148	175	
	AG	5,023,200	06/91	Blewer et al.	437	187	
	AH	5,470,801	11/95	Kapoor et al.	437	238	
	AJ	5,192,834	03/1993	Yamanishi et al.			
	AJ	5,461,003	10/1993	Havemann et al.			
MBC	AK	5,744,399	04/1998	Rostoker et al.			
FOREIGN PATENT DOCUMENTS							
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	AO						
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
MBC	AR			Togo, M., "A Gate-side Air-gap Structure (GAS) to Reduce the Parasitic Capacitance in MOSFETs", 1996 Sympos. on VLSI Technology Digest of Technical Papers, IEEE 1996, pp. 38-39.			
MBC	AS			Anand, M.B., "NURA: A Feasible, Gas-Dielectric Interconnect Process", 1996 Sympos. on VLSI Technology Digest of Technical Papers, IEEE 1996, pp. 82-83.			
MBC	AT			Watanabe, H., "A Novel Stacked Capacitor with Porous-Si Electrodes for High Density DRAMs", Microelectronics Research Laboratories, NEC Corp., date unknown, pp. 17-18.			
EXAMINER		[Signature]			DATE CONSIDERED		
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Werner Juegling et al.PRIORITY FILING DATE
July 14, 1998PRIORITY GROUP
2813

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<i>ML</i>	AA	5,171,713	12/1992	Mathews			
	AB	4,561,173	12/1985	TeVelde			
	AC	5,141,896	08/1992	Katoh			
	AD	5,736,425	04/1998	Smith et al.			
	AE	5,807,607	09/1998	Smith et al.	2		
	AF	5,950,102	09/1999	Lee			
	AG	5,882,978	03/1999	Srinivasan et al.			
	AH	5,804,508	09/1998	Goode et al.			
	AI	5,103,288	04/1992	Sakamoto et al.			
	AJ	6,028,015	02/00	Wang et al.			
	AK	5,883,014	03/1999	Chen et al.			
	AL	5,861,345	01/1999	Chou et al.			
	AM	6,001,747	12/1999	Annappagada			
<i>ML</i>	AN	S/N 09/948,372		Leonard Forbes et al.			10/9/97

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
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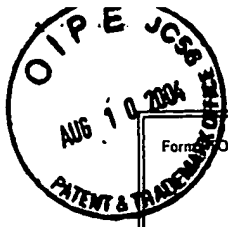
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>ML</i>	AQ	Peter Singer (Editor-in-Chief): "The New Low-k Candidate: It's a Gas"; Technology News, March 1989, 1 page
<i>ML</i>	AR	ABSTRACT: Anderson, R.C. et al., "Porous Polycrystalline Silicon: A New Material For MEMS", Jnl. Of Microelectromechanical Systems (Mar. 1994), Vol. 3, No. 1, pp. 10-18
<i>ML</i>	AS	Stanley Wolf, "Silicon Processing for the VLSI Era", Vol. 1, Sunset Beach, CA; Lattice Press, pp. 429-437.

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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Micron Technology, Inc.				
				FILING DATE March 28, 2001		GROUP 2812		
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
<i>MA</i>	AA	5,970,360	10-19-99	Cheng et al.				
	AB							
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
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EXAMINER <i>Michael J. Schmitt</i>				DATE CONSIDERED <i>07/8/04</i>				
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U.S. PATENT DOCUMENTS

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AA						
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FOREIGN PATENT DOCUMENTS

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AM							
AN							
AO							
AP							
AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

MSL	AR	Stanley Wolf, "Silicon Processing for the VLSI Era", 1986, pp 1-8.
	AS	
	AT	

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*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
PSL	AA	6,156,374	12-2000	Forbes et al.			
PSL	AB	5,286,668	02-1994	Chou			
	AC						
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	AL						

FOREIGN PATENT DOCUMENTS

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							Yes	No
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	AO							
	AP							
	AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

	AR	Seeley, Wolf, Silicon Processing for the VLSI Era, 1986, pp 1-3.	ALREADY CONSIDERED					
	AS							
	AT							

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Form PTO-159 <div style="border: 1px solid black; border-radius: 50%; padding: 10px; display: inline-block; transform: rotate(-15deg);"> OFFICE APR 29 2004 PATENT </div>		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1599		PRIORITY SERIAL NO. 09/115,339	
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	AC	3,998,662	12/21/76	Anthony et al.			
	AD	4,063,901	12/20/77	Shiba			
	AE	4,180,416	12/25/79	Brock			
	AF	5,488,015	1/30/96H	Stevenson et al.			
	AG	5,496,773	3/5/96	Rhodes et al.			
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	AJ	5,527,737	6/18/96J	eng			
	AJ	5,583,078	12/10/96	Osenbach			
	AK	5,599,745	2/4/97	Reinberg			
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	AR	HOMMA, TETSUYA, "Low Dielectric Constant Materials and Methods for Interlayer Dielectric Films in Ultralarge-Scale Integrated Circuit					
		Multilevel Interconnections", <u>Materials Science & Engineering</u> , R23, pp. 243-285 (1998)					
	AS	ABSTRACT: Townsend, P.H., et al., "Silk Polymer Coating With Low Dielectric Constant and High Thermal Stability for ULSI Interlayer					
		Dielectric", <u>The Dow Chemical Company</u> , Midland, MI, 9 Pages, (Undated)					
	AT	PRODUCT BROCHURE and MATERIAL SAFETY DATA SHEET, "Interlayer Dielectric", <u>JSR Microelectronics</u> , 12 Pages (1997)					
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Form PT-1019P		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1599		PRIORITY SERIAL NO. 09/115,339	
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	AB	4,561,173	12/1985	TeVelde			
	AC	5,141,896	08/1992	Katoh			
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	AE	5,807,607	09/1998	Smith et al.			
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	AG	5,882,978	03/1999	Srinivasan et al.			
	AH	5,804,508	09/1998	Gnade et al.			
	AI	5,103,388	04/1992	Sakamoto et al.			
	AJ	6,028,015	02/00	Wang et al.			
	AK	5,883,014	03/1999	Chen et al.			
	AL	5,861,345	01/1999	Chou et al.			
	AM	6,001,747	12/1999	Annappagada			
	AN	S/N 09/948,372		Leonard Forbes et al.			10/9/97
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	AR	ABSTRACT: Andersson, R.C. et. al., "Porous Polycrystalline Silicon: A New Material For MEMS", Jnl. Of Microelectromechanical Systems (Mar. 1994), Vol. 3, No. 1, pp. 10-18					
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AC	5,691,565	11/25/97	Manning			
AD	5,691,573	11/25/97	Avanzino et al.			
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AF	3,954,523	05/76	Magdo et. al.	148	175	
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AJ	5,461,003	10/1995	Havemann et al.			
AK	5,744,399	04/1998	Rostoker et al.			

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FOURTH EDITION DOCUMENTS									
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								Yes	No
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	AO								
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AR	Togo, M., "A Gate-side Air-gap Structure (GAS) to Reduce the Parasitic Capacitance in MOSFETs", 1996 Sympos. on VLSI Technology Digest of Technical Papers, IEEE 1996, pp. 38-39.
AS	Anand, M.B., "NURA: A Feasible, Gas-Dielectric Interconnect Process", 1996 Sympos. on VLSI Technology Digest of Technical Papers, IEEE 1996, PP. 82-83.
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